

positioning a chemical vapor deposition coating apparatus over a tin bath containing a glass ribbon having a temperature of at least about 400° C (752° F);

directing a titanium dioxide precursor through said chemical vapor deposition apparatus over a surface of the glass ribbon heated to said temperature; and

thereafter annealing the glass ribbon,

whereby said layer of titanium dioxide is produced.

²³/₆₃. (Amended) A method according to claim ¹²/₅₂, the improvement further comprising: depositing over a surface of said float ribbon as the float ribbon is formed in said tin bath a sodium ion diffusion barrier layer comprising silicon oxide and having a thickness of at least about 100 Å over a surface of said float ribbon and depositing in said tin bath said photocatalytically-activatable self-cleaning coating over said sodium ion diffusion barrier layer.

²⁴/₆₄. (Amended) A method comprising the steps of:
providing by a float manufacturing process a glass article having at least one surface;

depositing in a tin bath during said float manufacturing process a photocatalytically-activatable self-cleaning coating over the surface of the article by chemical vapor deposition so that the coating has titanium dioxide in at least the crystalline phase and has a thickness ranging from at least 100 Å to less than 1 micron.

³⁶/₇₆. (Amended) A method comprising the steps of:
providing by a float glass manufacturing process a glass article having at least one surface;

depositing a sodium ion diffusion barrier coating over the surface of the article by chemical vapor deposition in a tin bath during the glass manufacturing process; and

depositing at a temperature in the range of from about 538° to below about 800°C (1000° to 1472° F) a photocatalytically-activatable self-cleaning coating over the

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barrier coating so that the photocatalytically-activatable self-cleaning coating comprises titanium dioxide in at least the crystalline phase and has a thickness ranging from at least about 100 Å to less than 1 micron.

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³⁸₃₇. A method according to claim ³⁴₇₆, further comprising the step of exposing the photocatalytically-activatable self-cleaning coating to ultraviolet radiation whereby a photocatalytically-activated self-cleaning coating is produced.

³⁹₇₉. A method according to claim ³⁶₇₆, wherein the glass ribbon is at a temperature of 648°C to 800°C.
